

Investigation of Speciation in III-V Wet Etching to Mitigate Hazardous Product Formation

(Task Number: 425.049)

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Other Researchers:

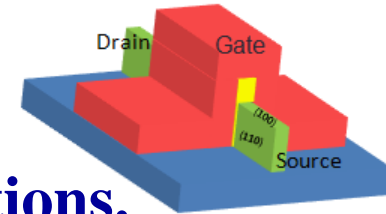
- **Tim Corley, Hydrology and Water Resources**

Cost Share (other than core ERC funding):

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Objectives

- **III-V materials allow for manufacturing beyond the limits of silicon.**
- **Predict the species produced by wet etching III-V semiconductors.**
 - **Use thermodynamics of liquid phase solutions.**
 - **Vary pH, molarity, solution chemistry.**
- **Validate speciation at select process conditions.**
 - **Measure gas and liquid phases.**
 - **Mass balance on Ga and In.**
 - **Total**
 - **Species**
 - **Scale bench top experiments to full wafer.**
 - **Start with aqueous solutions of HCl and H₂O₂.**



FinFET

ESH Metrics and Impact

Marker	Max 30 day average	Source
Total Toxic Organics	1.37 mg/l	40 CFR 469.24
Arsenic	0.83 mg/l	40 CFR 469.24
pH	6-9	40 CFR 469.24

Compound	Exposure	Hazard
In ₂ O ₃ , In(OH) ₃	Inhalation via Occupational Exposure	Lung Cancer, Pulmonary Alveolar Proteinosis, Emphysema
AsH ₃	Chronic Exposure >0.05 ppm	Anemia, Cardiovascular Disease, Peripheral Neuropathy

Cummings, Kristin J. et al. "Indium Lung Disease." Chest 141.6 (2012): 1512–1521. PMC. Web. 28 Mar. 2015.

Arsine; MSDS No. P-4565-J [online]; Praxair: Danbury Ct, March 23, 2015

III-V Wet Etching

- Define concentrations of all reaction products as function of processing conditions including waste disposal.
 - $[\text{H}_2\text{O}_2] = 0.0001 - 8 \text{ M}$
 - $[\text{HCl}] = 0.01-2 \text{ M}$
- Scale species concentrations in gas and liquid phase to identify potential situations that do not meet regulations.
 - Limitations of current hydride sensors.
 - Reports of 97-99% recovery of indium using MRT gels.

Approach

- Use thermodynamics to identify the species to expect in the gas and liquid phases for different pairings of III-V material and etching chemistry.
- Close a mass balance on the etching process by measuring total masses of group III and V atoms in gas and liquid.
- Measure partitioning of species in gas and liquid for different pairings of III-V material and etching chemistry.
 - Especially important to measure In in aqueous phase to determine whether both chloride and hydroxide present.

Thermodynamic Modeling

- Software packages used to predict speciation.
 - PHREEQCi
 - Designed by USGS for aqueous systems.
 - STABCAL
 - Commercial
- Both software packages make use of thermodynamic databases or manually entered parameters.
- Validate with experiments.
- Use to guide selection of techniques to measure species concentration.

Example HCl and H₂O₂ System

- HCl (0.01 – 1.76 M) and H₂O₂ (1.0 E-4 – 8 M) based solutions are commonly used for etching III-V materials.
 - Characterized by a redox potential in the range of 0.70 – 1.1 V.
- Potential-pH (Pourbaix) diagrams were constructed for the following conditions.

[In] = 1.0 E-5 M; [Cl⁻] = 0.01 or 1.76 M

pH range of -1 to 7

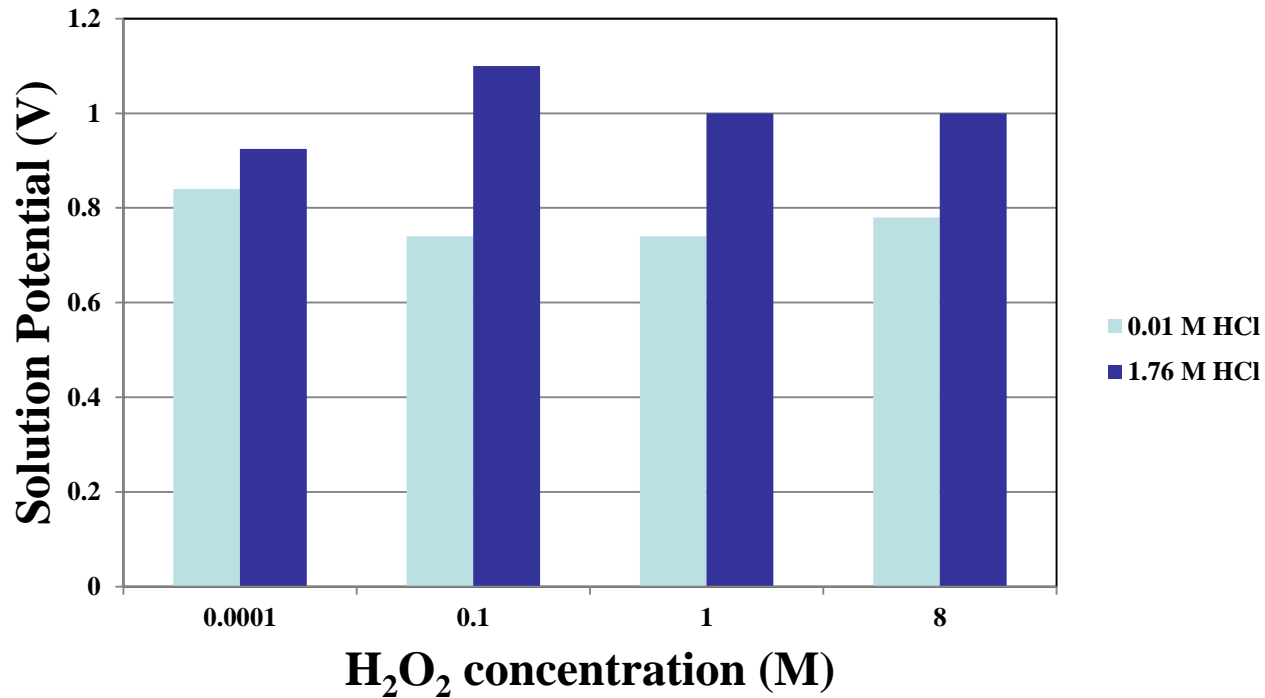
Potential range of 0 – 2 V

- Distribution-potential diagrams were constructed for the following conditions.

[In] = 1.0 E-5 M; pH=2 or -0.24

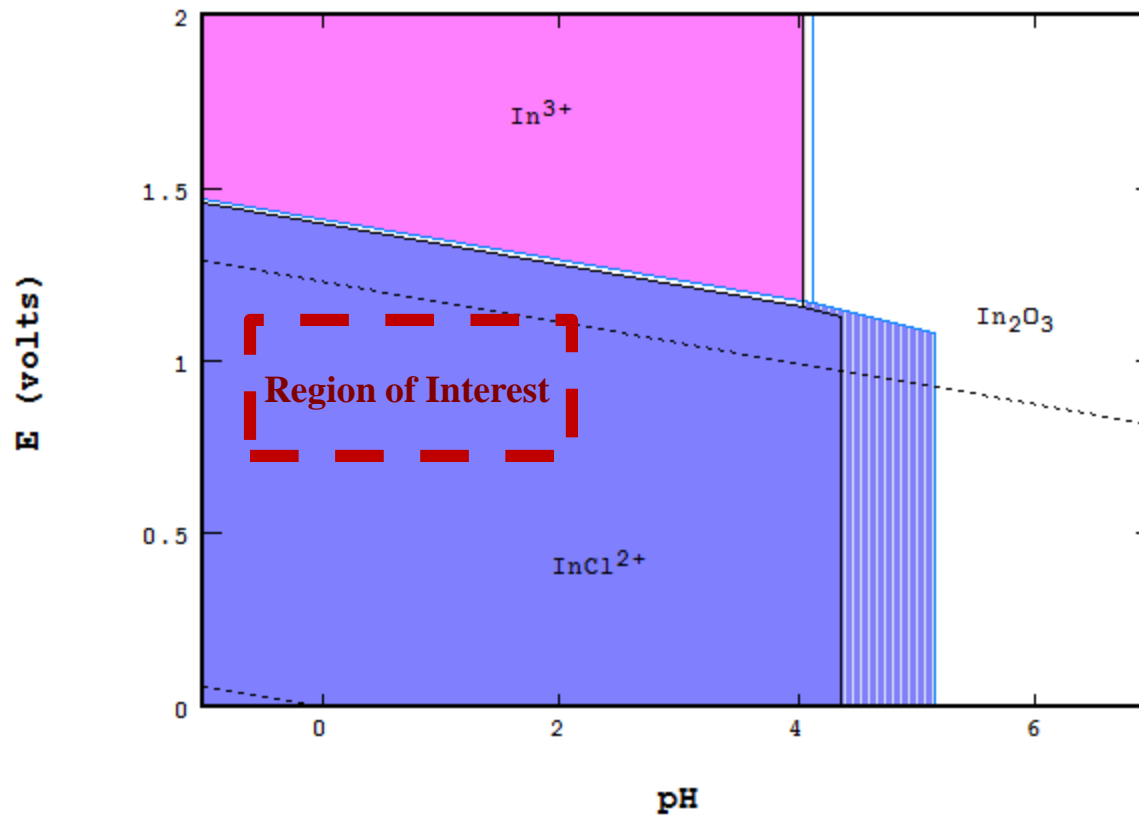
Potential range of 0 – 2 V

Solution Potential as a Function of H_2O_2 Concentration



Potential-pH Diagrams

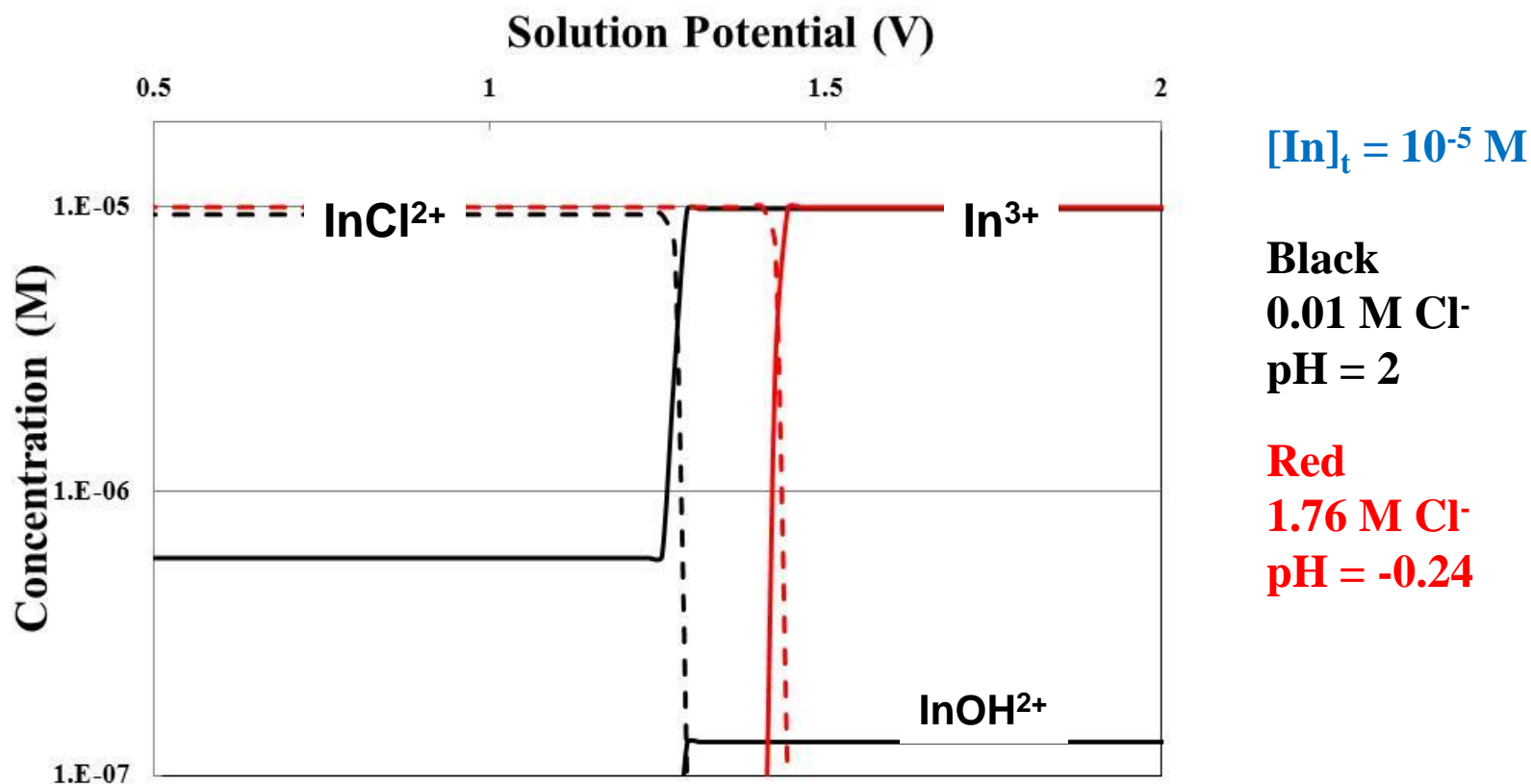
In (10^{-5} M) – Cl⁻ (0.01 or 1.76 M) – Water System



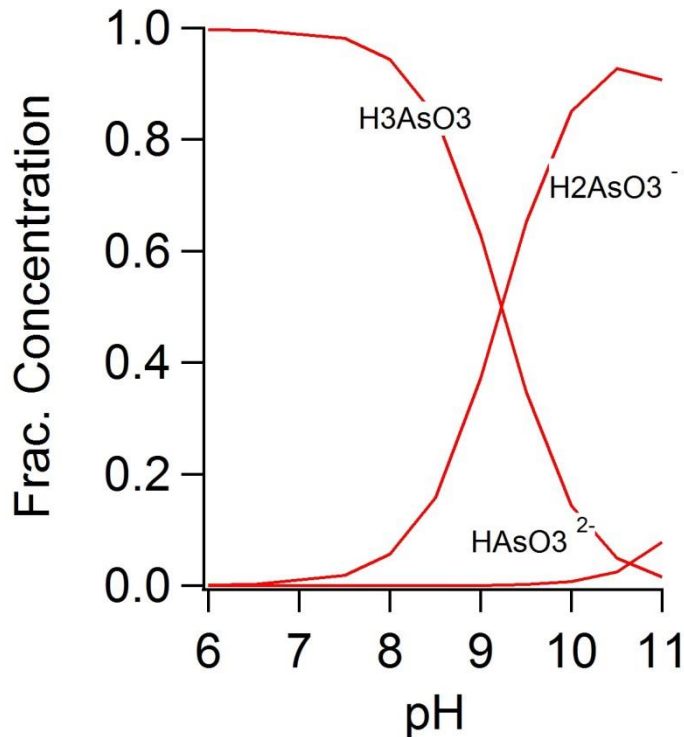
Comparison

Increase in
Cl⁻ increases
the stability
region of
 InCl^{2+}

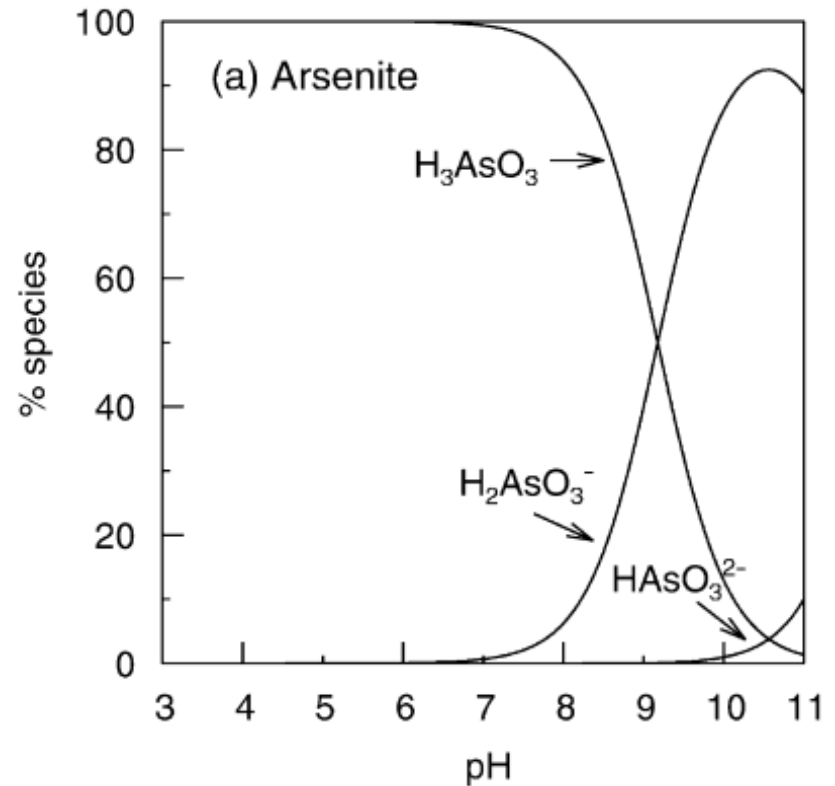
Distribution of Indium Species as a Function of Solution Potential



Arsenic Distribution in PHREEQCi



- **Good agreement between PHREEQCi and diagram from literature.**



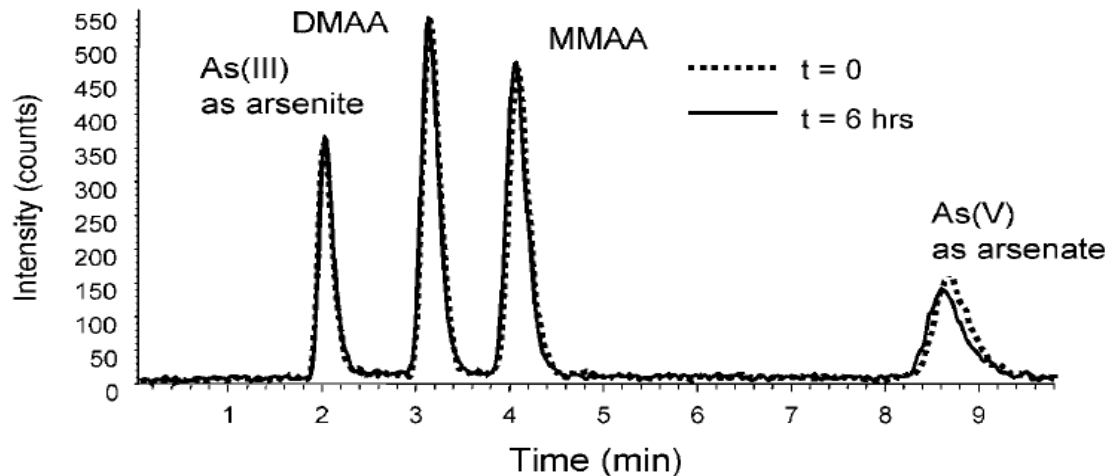
Smedley, P.I, and D.g Kinniburgh. "A Review of the Source, Behaviour and Distribution of Arsenic in Natural Waters." *Applied Geochemistry* 17.5 (2002): 517-68. Web.

Species Monitored in Vapor and Liquid Phases

Equipment	Purpose	Detection Range
Differentially Pumped Mass-Spec	Vapor Phase Detection	> 1 ppt sensitivity
ICP-MS	Liquid Phase Detection	< 10 µg/l
ICP-OES	Liquid Phase Detection	> 10 µg/l

Measurement Example

Compound	Phase	Detection Method
Aqueous As(III), As(V) species	Liquid	HPLC-ICP-MS
AsH ₃	Vapor	ICP-MS FTIR: 2115.2, 906.75, 1126.42, 999.22 cm ⁻¹

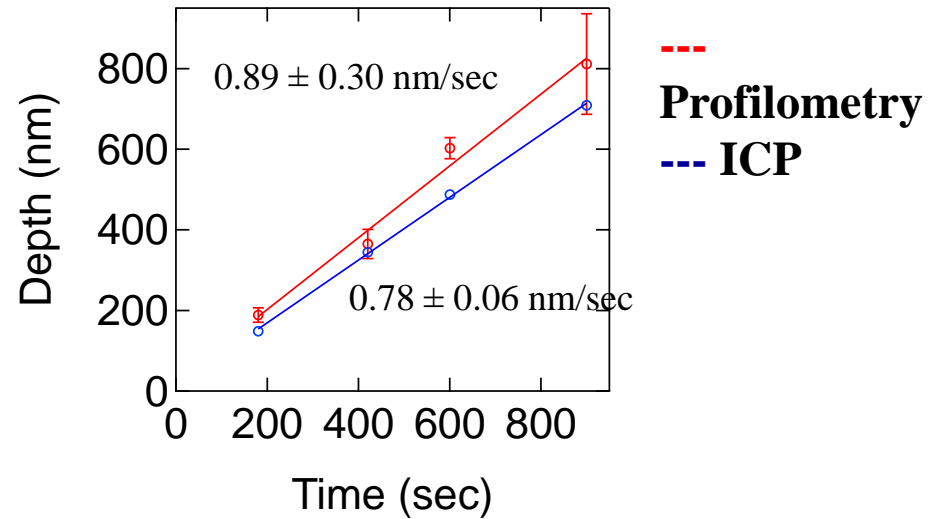
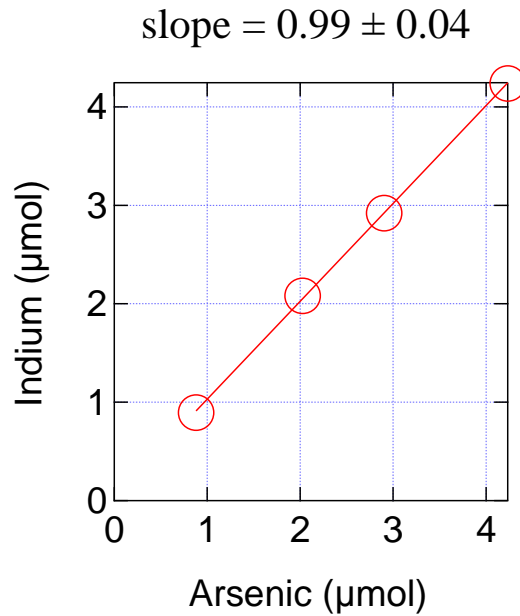


Day, Jason A et al. "A Study of Method Robustness for Arsenic Speciation in Drinking Water Samples by Anion Exchange HPLC-ICP-MS." *Analytical and Bioanalytical Chemistry* 373.7 (2002): 664-68. Web.

Total Mass Balance Experiment

- **InAs (100)**
 - **1x1 cm² samples patterned and unpatterned**
- **Etching rate**
 - **Unpatterned**
 - **Timed submersion in aq. [HCl]=0.01 M and [H₂O₂]=0.1 M.**
 - **Aliquots removed at discrete time intervals and analyzed by ICP-MS.**
 - **No gas phase data.**
 - **Patterned**
 - **Etch, remove photoresist, and measure amount etched by profilometry.**

Total Mass Balance and Etching Rate



1:1 In to As stoichiometry in solution suggests all species remain in liquid phase.

InAs(100) etching rate (nm/s) based on profilometry and ICP-MS agrees.

Conclusions

- **InCl²⁺ species stable in solution based on thermodynamic model at concentrations and solution potentials of interest.**
- **Closed total mass balance on InAs(100) etching reaction based on close comparison of profilometry and ICP-MS etching rate data.**
- **In/As = 1:1 in solution suggests all species remain in liquid.**

Future Work

- **Develop thermodynamic calculations.**
 - **Expand databases for use in both PHREEQCi and STABCAL.**
 - **Replicate simulations in both sets of software to ensure continuity between programs.**
 - **Extend to binary systems**
- **Start speciation experiments.**
 - **Complete differentially-pumped mass spec to measure gas phase species.**
 - **Develop liquid phase separation procedures for III-V etching products.**

Industrial Interactions and Technology Transfer

Industrial liaisons:

Reed Content, Global EHS, Global Foundries, Santa Clara, CA

Brian Raley, Global EHS, Global Foundries, Austin, TX

David Speed, Microelectronics, IBM, Hopewell Junction, NY